

IN THE ABSTRACT:

Please cancel the current abstract and insert the following new abstract therefor:

-- An exposure apparatus for exposing a substrate to light via a mask. The apparatus includes a projection optical system configured to project a pattern of the mask onto the substrate, a cover configured to surround a path of light from the projection optical system toward the substrate, a first supply port arranged inside the cover and configured to supply inert gas inside the cover, a first recovery port arranged inside the cover and configured to recover gas inside the cover, a second supply port arranged outside the cover and configured to supply gas outside the cover, and a second recovery port arranged outside the cover and configured to recover gas outside the cover. The first direction from the first supply port to the first recovery port and a second direction from the second supply port to the second recovery port oppose each other at an angle not greater than  $90^\circ$ . --